DIGITRON SEMICONDUCTORS

Metal Oxide Field Effect Transistor (MOSFET) HR flow

All parts are screened per MIL-PRF-19500, JANTX Level and the device detail specification. All testing is performed at room temperature, unless indicated otherwise. For testing at high and low temperatures, Group A testing is required.

| | Test | Method | Conditions / Notes |
|----|--|-------------------------|---|
| 1 | Temperature Cycling | MIL-STD-750 Method 1051 | Test condition C or maximum storage temperature, whichever less. 20 cycles, 10 minutes per extreme. |
| 2 | Interim Electrical Testing | | DC parameters per device detail specification. |
| 3 | Gate Temperature Reverse Bias Burn-in | MIL-STD-750 Method 1042 | Condition B. 48 hours at 150° C and 80% of rated V_{GS} . |
| 4 | Interim Electrical Testing | | DC parameters per device detail specification. |
| 5 | High Temperature Reverse Bias Burn-in | MIL-STD-750 Method 1042 | Condition A. 160 hours at 150°C and 80% of rated V_{DS} . |
| 6 | Final Electrical Testing | | DC parameters per device detail specification. |
| 7 | Delta Calculation | | Delta parameters and limits per device detail specification. |
| 8 | PDA Calculation | | 10 percent defective allowed. |
| 9 | Seal Test Fine Leak | MIL-STD-750 Method 1071 | Condition G or H |
| 10 | Seal Test Gross Leak | MIL-STD-750 Method 1071 | Condition C |

Notes:

- 1. Testing varies in accordance with the device detail specification.
- 2. Specific customer testing needs may be accommodated into any testing flow (selection tests, temperature requirements, special tests).